



“Integrating Thin Film Resistors into Organic Substrates for Module and Integrated Circuit (IC) Packaging”

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SPEAKERS



John Andresakis

Director of Business Development, Quantic Ohmega Ticer

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John Andresakis has over 40 years of experience manufacturing printed circuit boards and related products. He joined Quantic Ohmega-Ticer in January 2023 and is now the Director of Business Development. He is working on expanding the market for the company's novel thin film resistor technology.



Andreas Schilloff

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Andreas Schilloff joined Green Source Fabrication in 2018, bringing along many years of PCB fabrication experience from I3 Electronics and Sanmina Corporation. In addition, Andreas has an ME/EE degree from RIT. From 2018 through the present time as Principal Product Engineer, he has contributed to expanding GSF capabilities in producing third-party products, from the aspects of NPI/ Process/ Product engineering.





Agenda

- Introductions and Benefits
- Resistor/Conductor Foil Formation
- Manufacturing Process- mSAP Overview
- Test Vehicle Design
- Experimental Results
- Optimization Strategies
- Future Directions and Opportunities
- Conclusion



Introduction and Benefits

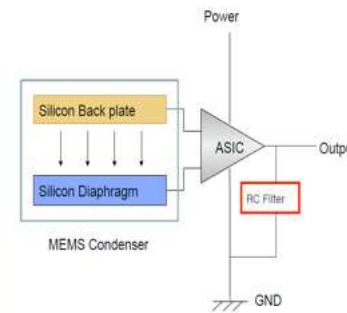
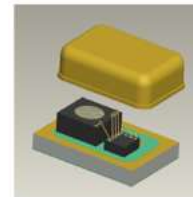


- Integration of thin film resistors into organic substrates
- Key Benefits:
 - Significant miniaturization
 - Reduced need for discrete resistors
 - Space conservation on substrate surface
 - Compatible with existing production methods
 - Improved signal integrity



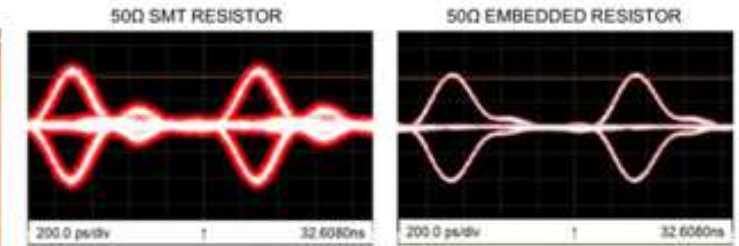
Surface Mount

Embedded



EMC@217Hz & 1KHz improved 20dBV from 500 to 2800MHz

Embedded Thin Film Resistors SI Improvement



Eye diagrams show 30% reduced noise at 1 Gb/s using thin film resistor

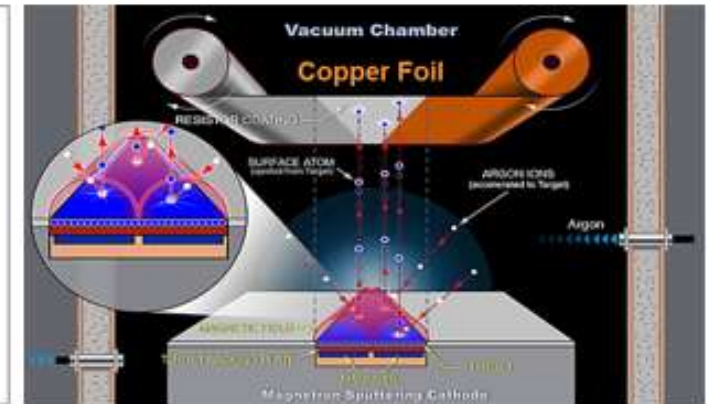
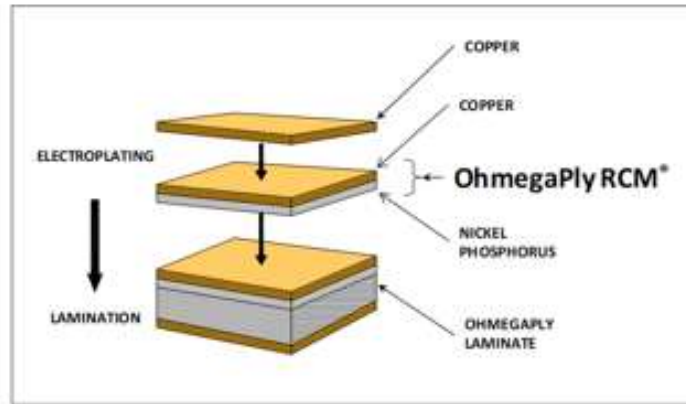
Courtesy of Applied Laser Technology



Resistor/Conductor Foil Formation



- Resistive Layer Deposition:
 - Electroplating Deposition
 - Sputtering Deposition
- Material Selection:
 - NiCr selected for optimal properties
 - Low temperature coefficient of resistance
- Carrier Foil Method Benefits:
 - Stable, flat surface
 - Precise control
 - Easy handling
 - Sub-micron thickness capability



Resistivity = Ohms/square

$$R = R_s \left(\frac{L}{W} \right)$$

L1 = W1
N1 = 1
R1 = 25 Ohms

L2 = W2
N2 = 1
R2 = 25 Ohms

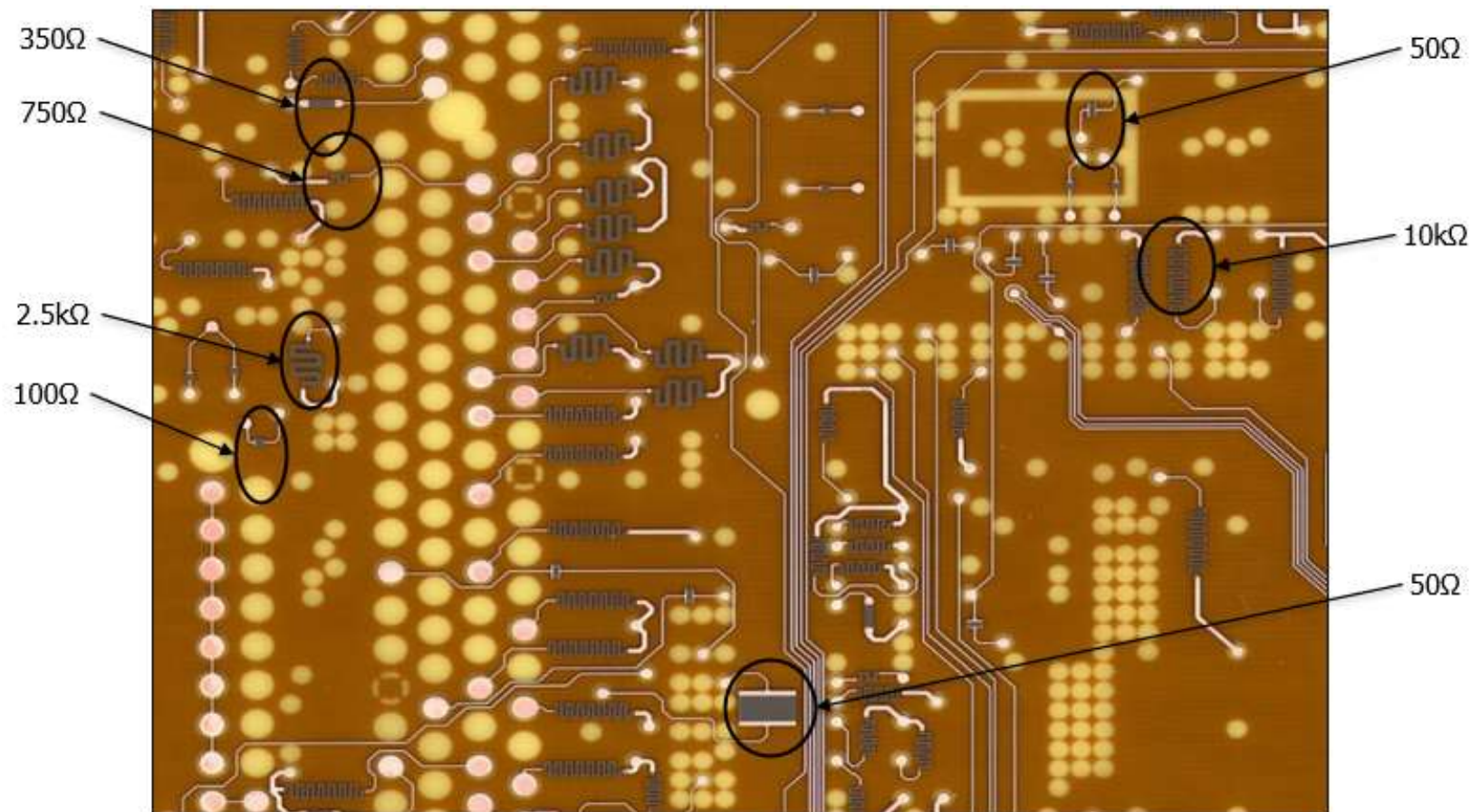
L3 = W3
N3 = 1
R3 = 25 Ohms

Length

Width

Copper Trace Resistor Copper Trace

Designing with Ohms per Square (100 OPS Example)



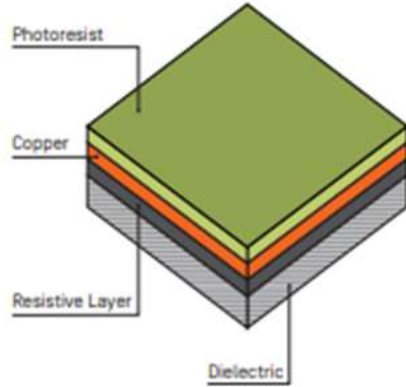
One sheet resistivity can make orders of magnitude resistors



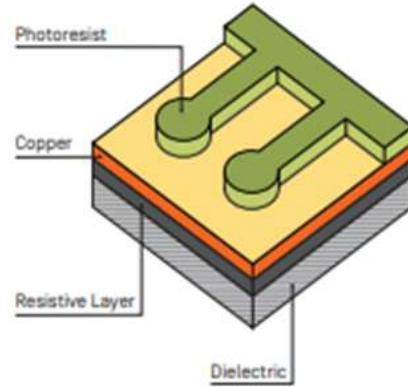
Manufacturing Process- Standard Subtractive Method



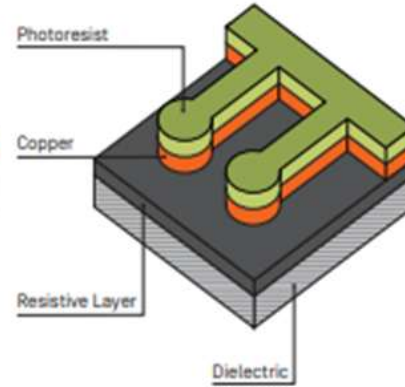
Step 1: Apply Photoresist to Laminate



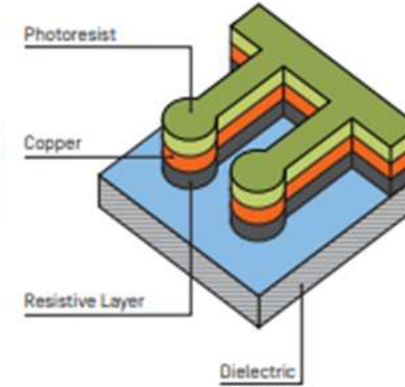
Step 2: Print Image, Develop off Photoresist



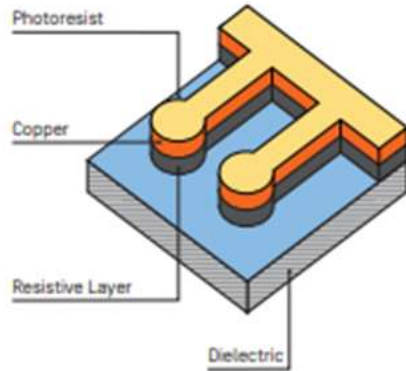
Step 3: First Etch to Define Copper Circuitry & Resistor Width



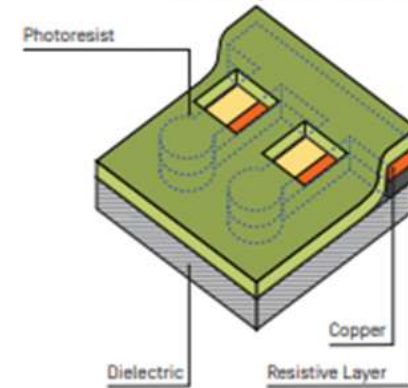
Step 4: Second Etch to Eliminate Resistive Alloy, if Applicable



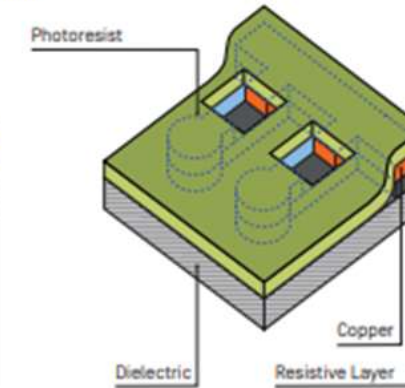
Step 5: Strip Photoresist



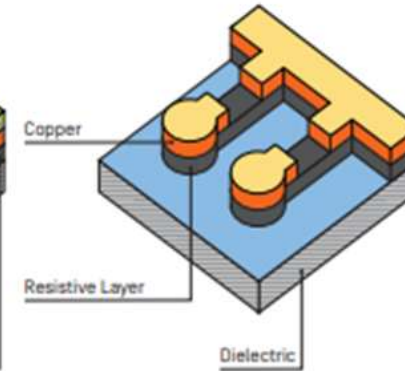
Step 6: Apply Photoresist, Print Resistor Image, Develop off Photoresist



Step 7: Third Etch to Define Resistor Length



Step 8: Strip Photoresist



Manufacturing Process- mSAP Overview

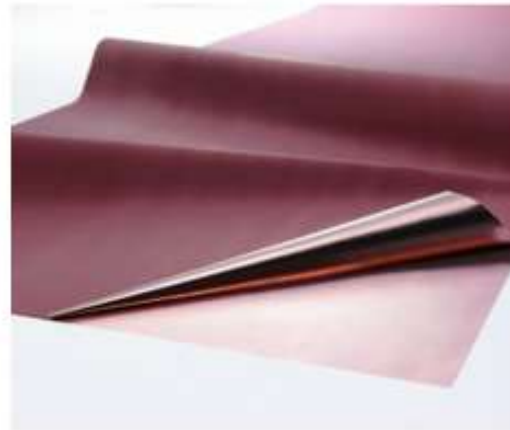


Seed Layer Preparation Methods:

- Direct Metallization
- Etching Down of 9-18 micron Foil
- Sacrificial Carrier Foil Method (preferred)

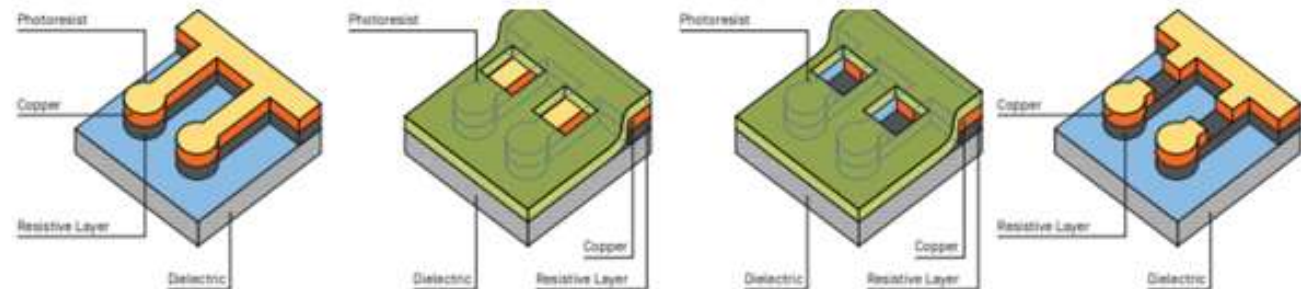
Process Steps:

- Seed layer creation
- Photoresist application and patterning
- Trace plating (12-15 microns)
- Photoresist stripping
- Quick etch for seed layer and **resistor material** removal.
- 2nd Imaging/etching steps to define resistors
 - *Note: Needed when using embedded resistors*



Carrier Foil

- 18 um carrier
- 3 um seed layer

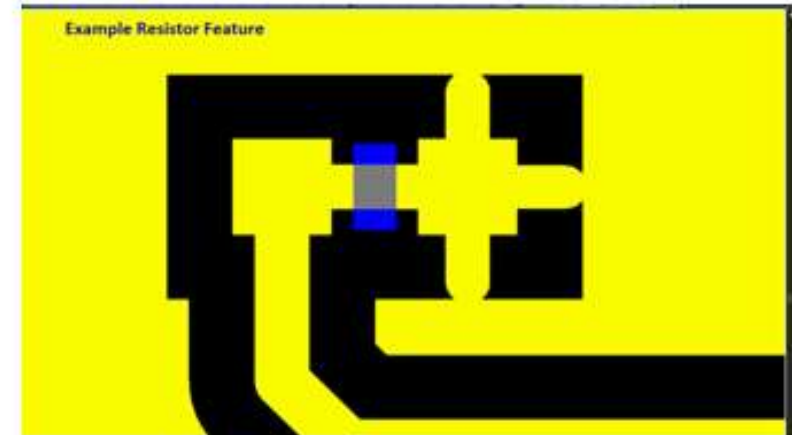
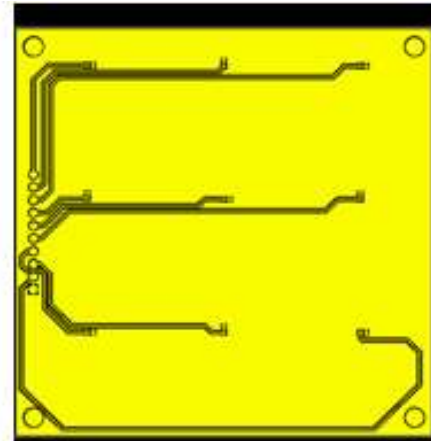


2nd Imaging/Etching steps

Test Vehicle Design



- 6-layer (2+2+2) substrate design
- Materials Used:
 - Core: Panasonic R-1515V (low CTE)
 - Build-up prepreg: AGC fastRise™ HF
 - Copper layers: 18µm, 9µm, and 3µm (after carrier removal) thicknesses
 - Resistor material on layer 2 (100 OPS NiCr)



Layer	Stack up	Base Thickness (µm)	Processed Thickness (µm)	Isolation Distance (µm)	Impedance (Ω)	Copper Layer Type	Copper Coverage	Description
1		8.50	15.00			Signal	0.00	3um-007_3_ED_AC-007-ALUM-9um-JTCS-P1_20_X_26_NONE
2		51.00	3.23	48.75	48.75	Mixed	85.00	RF-HF-051_BP_51um_18.5_X_24.5
3		3.00	15.00			Mixed	85.00	3um-18um_3_ED_7C100-NIC_18.5_X_24.5
4		51.00	3.23	48.50	48.50	Mixed	85.00	RF-HF-051_BP_51um_18.5_X_24.5
5		17.27	25.00			Plane	90.00	R1515V_0160_H_VLF_H_VLF_4-2118_180_X_24
6		400.00	4.40	400.00	400.00	Plane	90.00	
		17.27	25.00			Plane	90.00	
		51.00	3.23	48.50	48.50	Mixed	85.00	RF-HF-051_BP_51um_18.5_X_24.5
		3.00	15.00			Mixed	85.00	3um-18um_X_ED_MT18EX_20X26
		51.00	3.23	48.75	48.75	Mixed	85.00	RF-HF-051_BP_51um_18.5_X_24.5
		8.50	15.00			Signal	0.00	3um-007_3_ED_AC-007-ALUM-9um-JTCS-P1_20_X_26_NONE

Copper Thickness = 110.000 | Dielectric Thickness = 394.504 | Solder Mask Thickness = 0.000 |
 Stack Up Thickness = 704.504 | Stack Up Thickness with Soldermask = 704.504

Notes
 buried vias are mainly for D-coupon/ reliability testing (both stacked and staggered)
 layers 2/5 are MSAP for resistor process
 outer are HF plated to finish at around 15um to demonstrate 150nm pitch BGA pattern



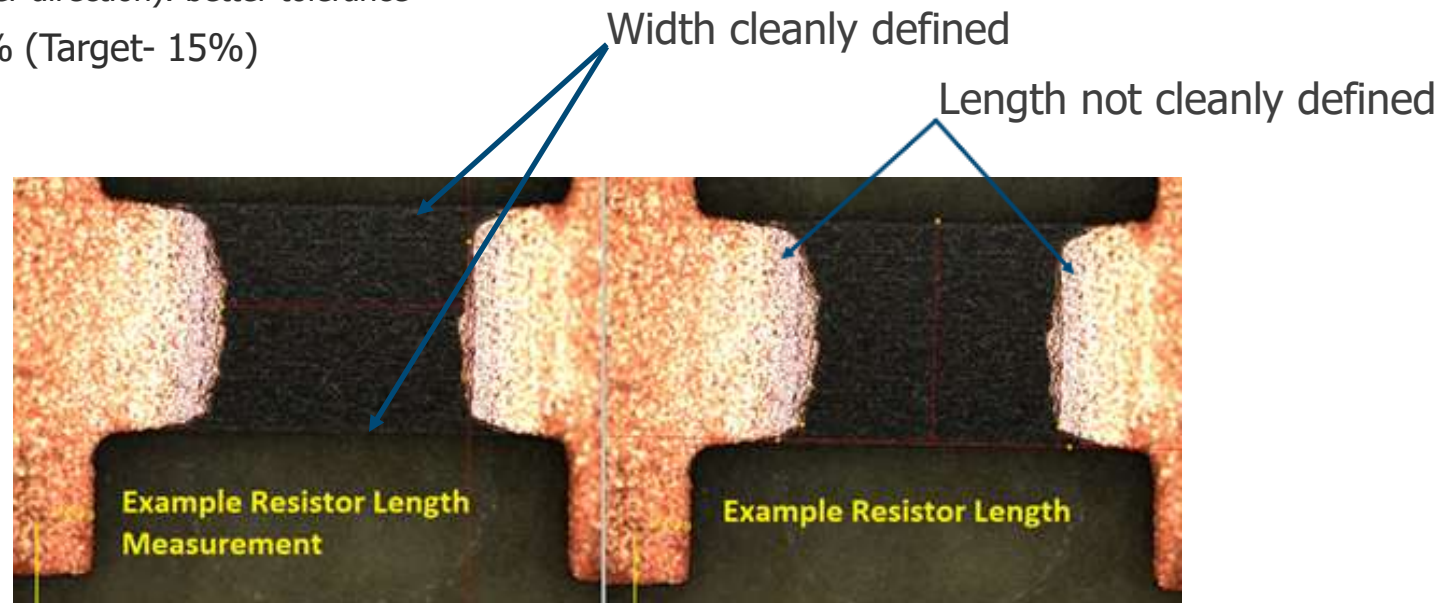
Experimental Results



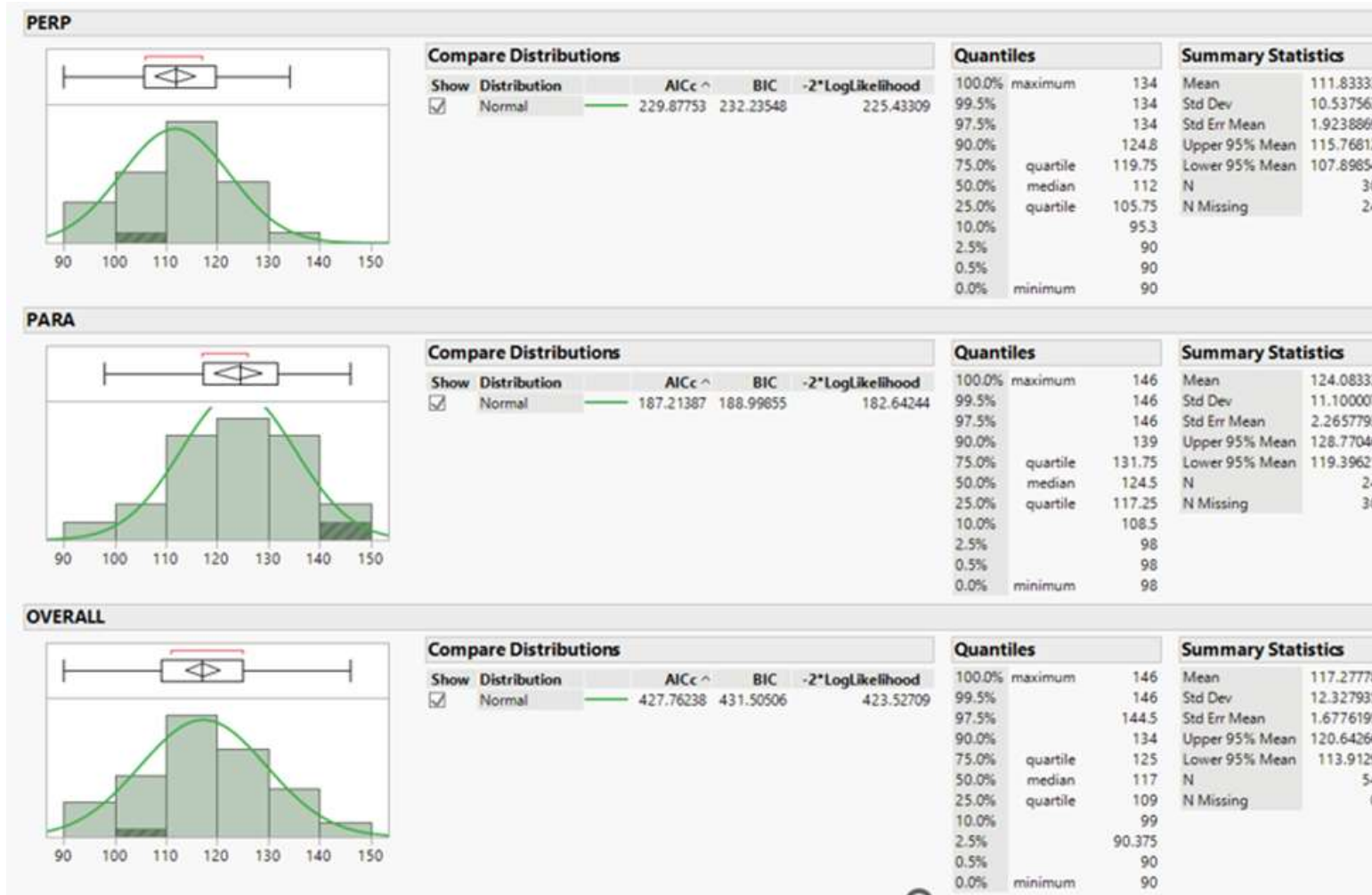
Target: 100 ohms resistors (0.01"(0.254mm) x 0.01"(0.254mm)) using 100 Ohms/square material

Key Findings:

- Successful embedding of resistors
- Good material adhesion to build-up film
- Orientation affects resistance values and tolerance
 - Perpendicular resistors (to etcher direction): better tolerance
- Overall tolerance: +/- 20-25% (Target- 15%)



Experimental Results



Note: For the size resistors used in this study, if made using the standard subtractive process, the tolerance can be > +/- 30%



Optimization Strategies



Design/Process Improvements:

- Orient resistors perpendicular to the etcher direction
- Alternative: 45° angle processing in etcher
- Enhance plating distribution
- Modified copper plating process (do not plate up over resistor areas)
- Utilize standard first article procedure

Material Improvement

- Optimize resistivity uniformity of resistor/conductor foil
- Utilize lower Ohms/square value (thicker coating is more uniform)



Future Directions and Opportunities



Upcoming Research:

- Tolerance Improvement
- Material characterization (CTE, peel strength, etc.)
- Long-term reliability testing
- High-frequency electrical testing (40+ GHz)

Industry Collaboration:

- Open to partnerships
- Focus on practical implementations
- Scaling opportunities



Conclusions



- We have demonstrated that thin film resistors can be embedded in organic packaging substrates using resistive layers on 3- μ m copper (with a carrier) using the mSAP process.
- We did not meet the targeted tolerance but have a path to improve.
- Modules and IC Packages can utilize the potential benefits of embedded resistors.
 - Miniaturization and/or increased functionality
 - Improved electrical performance
 - Improved reliability
- Seeking opportunities for collaboration



MORE INFORMATION

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Questions?

Thank You!

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